

Anomalous Scaling Behavior in Polymer Thin Film Growth by Vapor Deposition

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Abstract. As a first step to understand anomalous kinetic roughening with multifractality in recent experiments of the vapor deposition polymerization (VDP) growth, we study a simple toy model of the VDP growth in a (1+1)-dimensional lattice, along with monomer diffusion, polymer nucleation, limited active end bonding, and shadowing effects. Using extensive numerical simulations, we observe that the global roughness exponent is different from the local one. It is argued that such anomalies in VDP growth are attributed to the instability induced by the nonlocal shadowing effects on active ends of polymers. As varying the ratio of diffusion coefficient to the deposition rate by cosine flux, we also discuss the role of diffusion in kinetic roughening of the polymer thin film growth, which is quite different from that of the metal or semiconductor film growth. Finally, we suggest its (2+1)-dimensional version, which can be directly compared with experimental results.

Keywords: kinetic roughening, thin film, chemical vapor deposition

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1. Introduction

In the last several years, kinetic roughening of nonequilibrium steady states for the growth of thin films and multilayers has been an issue of considerable interest [1, 2]. This is motivated by the demand for smooth or regularly structured surfaces and interfaces for miniaturized functional films in science and technology. Such interest is explained by surface film characterization at the submicron level and the mechanisms that determine the film morphology and can contribute to achieving better control of the film properties in real applications.

Although lots of theoretical and experimental studies have shown the existence of kinetic roughening and in many cases revealed the occurrence of scaling exponents corresponding to a few universality classes, there is no general picture of kinetic roughening for the growth of polymer thin films. It is because the major efforts has been focused on the growth of metal and semiconductor thin films. Now that the polymer thin films are growing technological interest for molecular devices and microelectronic interconnects [3], only a few such studies are known as pioneering works where also show kinetic roughening with various scaling behaviors [4, 5, 6]. Among many techniques for the polymer thin film growth, vapor deposition polymerization (VDP) best describes the coating process of poly (*p*-xylylene) (PPX), also known by the trade name Parylene [7], where the monomer from the gas phase condenses on the substrate, reacts to form high molecular weight as an oligomer, and becomes a part of polymers. In the present study, we mimic such VDP processes, in term of a modified MBE-type growth model, discuss kinetic roughening of the polymer thin film growth by vapor deposition, and give a guideline for the VDP growth model studies to explain the experimental data from the growth of polymer thin films.

This paper is organized as follows: In Sec. 2, we describe our model for the VDP growth in a (1+1)-dimensional lattice and show the evolution of surface morphologies with and without shadowing effects caused by cosine flux. In Sec. 3, numerical results are presented for kinetic roughening with multifractality as measuring surface roughness, height-difference correlation functions, the density profile, height and step distributions. Finally, we discuss the physical origin of the anomalous scaling behaviors as well as polymer characteristics, and suggest a possible extension of the VDP model in a (2+1)-dimensional lattice to be compared with recent experimental data of PPX-C film growth. We conclude the paper in Sev. 4 with a brief summary and remark.

2. Model

We mimic the polymer thin film growth by the VDP process, in terms of a simple toy model was proposed by Bowie and Zhao [8] in a (1+1)-dimensional lattice with L sites, where we use periodic boundary condition in a spatial direction, x , and add the coalescence process of polymers to the original model.

During the VDP process, the monomer transport in the vacuum is very similar to

the conventional physical vapor deposition (PVD) process, i.e., molecular beam epitaxy (MBE) process for metals or semiconductors [1]. However, they are quite different in the nucleation and growth processes after the monomer is condensed on the substrate or the film surface. In the PVD/MBE process, monomers are stable once they attach to the nearest neighbors of any nucleated sites, so that the films get dense and compact as monomer diffusion increases. In contrast, they become stable in the VDP process only when they reach one of two active ends of a polymer chain, and the films get rough as monomer diffusion increases since it occurs along the polymer bodies. Other surface dynamics can also affect the growth differently in two cases. While surface diffusion, edge diffusion, step barrier effect are relevant to the PVD/MBE case, intermolecular interaction and chain relaxation are relevant to in VDP case besides monomer diffusion. Such difference gives a distinct dynamic behavior for the VDP film morphology.

Dynamic rules and updates

For the simplicity, we omit the chain relaxation in our model and consider only the following five processes (see Fig. 1):

Deposition

At each step, a monomer is activated into the system with a incidental angle θ to the vertical direction, which incidental angle follows the distribution of $\cos(\theta)$, not a collimated flux. This incidence of monomers with angle distribution is called as *cosine flux* [9] with the deposition rate F , the number of incident monomers per site for unit time.

Surface Diffusion

Before the activated monomers are stabilized, an incident monomer deposited onto the polymer body sides or substrate randomly wander from one site to another site along the polymer bodies or substrate with diffusion coefficient D at each deposition step, where D is the number of hopping per monomer for unit time. The surface growth is controlled by the ratio of the diffusion coefficient to the deposition flux, $G = D/F$. From now on we set $F = 1$ for convenience, such that $G = D$.

Nucleation

When two monomers are met on substrate or polymer bodies, they form a dimer as a polymer seed, i.e., oligomer, which is called as *nucleation (initiation)*. In contrast to the MBE growth where atoms can attach to the nearest neighbors of the nucleated sites, in the VDP growth the stabilization reaction occurs only at the active ends of a polymer chain, so-called active sites. Such active bonding in the VDP growth is a key ingredient as well as the cosine flux for monomer deposition.

Propagation

When a monomer reaches one of the active ends of a polymer, it is stabilized as the part of the polymer and at the same time it becomes the active end of the polymer. This is called as *chain propagation*.

Coalescence

In process of the chain propagation, it is possible that an active end of polymer meets that of another polymer. Then two polymers are merged into one long polymer. This process is called as *coalescence (polymer interaction)*. It is worth to note here that, for linear polymers, only the two ends of the chain are active, and are ready for reacting with monomers or other polymers. However, we do not allow the polymer loop. In other words, if one active end of a polymer meets the other side active end of itself, the two active ends cannot merge into a stabilized polymer loop and such a try is rejected.

Performing Monte Carlo (MC) simulations for the VDP growth model, we use the random sequential (continuous time) updating method, in terms of the deposition probability of an incident monomer, P_F , and the diffusion probability of an ad-monomer, P_D denoting as $P_F = \frac{FL}{DN_m + FL}$ and $P_D = 1 - P_F = \frac{DN_m}{DN_m + FL}$, respectively. Here N_m is the number of ad-monomers and L is the system size, Rewriting the probabilities by the ratio G of the diffusion coefficient D to the deposition rate F , $G = D/F$ and the ad-monomer density $\rho_m = N_m/L$, such that

$$P_F = \frac{1}{G\rho_m + 1}, \text{ and } P_D = \frac{G\rho_m}{G\rho_m + 1}.$$

The detailed procedure of our MC simulations is as follows: First, generate a random number, $p \in (0, 1]$. If $p < P_F$, a monomer is deposited on the polymer bodies or substrate by the cosine flux with a randomly chosen angle. Otherwise, a randomly chosen ad-monomer out of N_m monomers diffuses to a randomly chosen direction. Then, the final surface configuration is governed by the above five VDP processes. The MC time is updated as the unit of monolayer (ML) after every L monomers deposit.

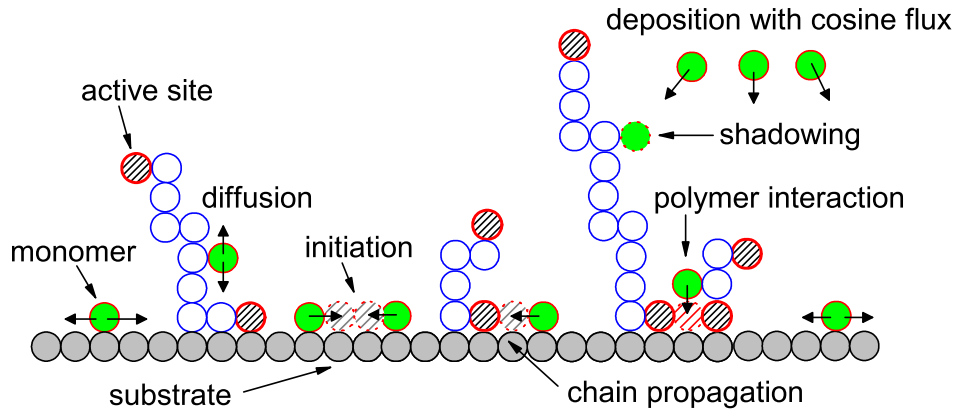


Figure 1. Five dynamic rules are illustrated as solid circles for monomers, open circles with thin lines for polymer bodies, and patterned circles with thick lines for active ends.

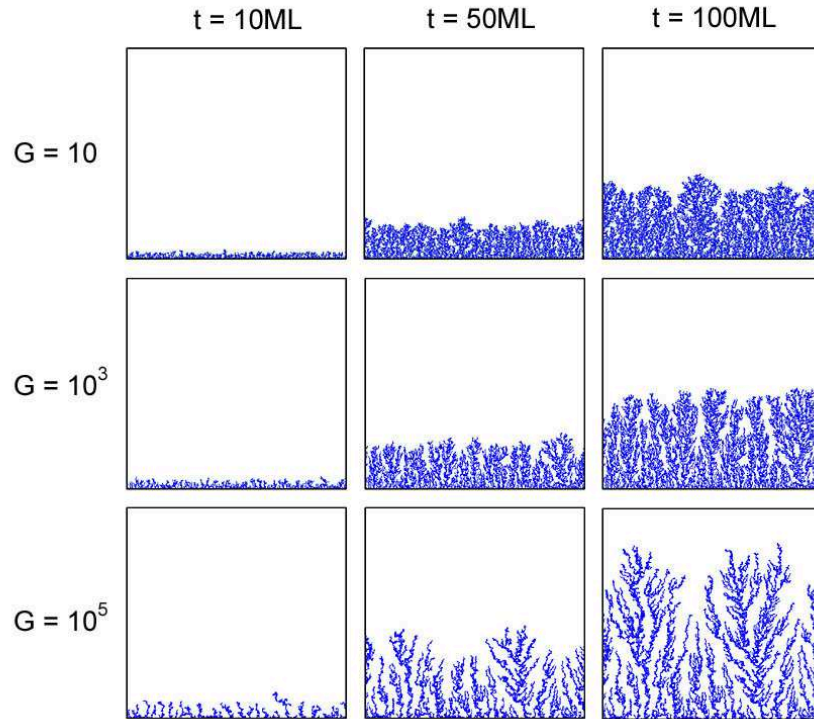


Figure 2. Snapshots of the VDP growth for $L = 512$ at three specific times, $t = 10$, 50 , and 100 ML for three values of $G = D/F$ with $F = 1$. From top to bottom panels, $G = 10$, 10^3 , and 10^5 .

Surface morphology

Before starting the detailed analysis and the main discussion, we check how the VDP growing surface evolves. As plotting the snapshots of the VDP model growth in Fig. 2 for various G values at three different stages of the film growth, we observe that the films exhibit tree-like characteristic morphologies and columnar structures with many voids and overhangs for all three cases of G as time elapses. Moreover, as G (diffusion coefficient) increases, the surface height grows rapidly and the columnar morphology becomes rougher and less denser. In order to figure out the origin of the characteristic columnar structure, we investigate the effect of the flux incident angle distribution on the VDP growth. When we fix the monomer incident angle to single vertical direction such as collimated flux, the surface columnar structures disappear as shown in Fig. 3 for all three cases of G . The evolution of surfaces by the VDP model growth is shown in Fig. 4, where we assume that the surface height is a single value of the highest position at the lateral site. One can see that, as G increases and t elapses, the columnar and grooved structure becomes much clearer.

In next section, we analyze this unusual VDP growing surface quantitatively with conventional physical quantities in surface growth models as well as polymer properties.

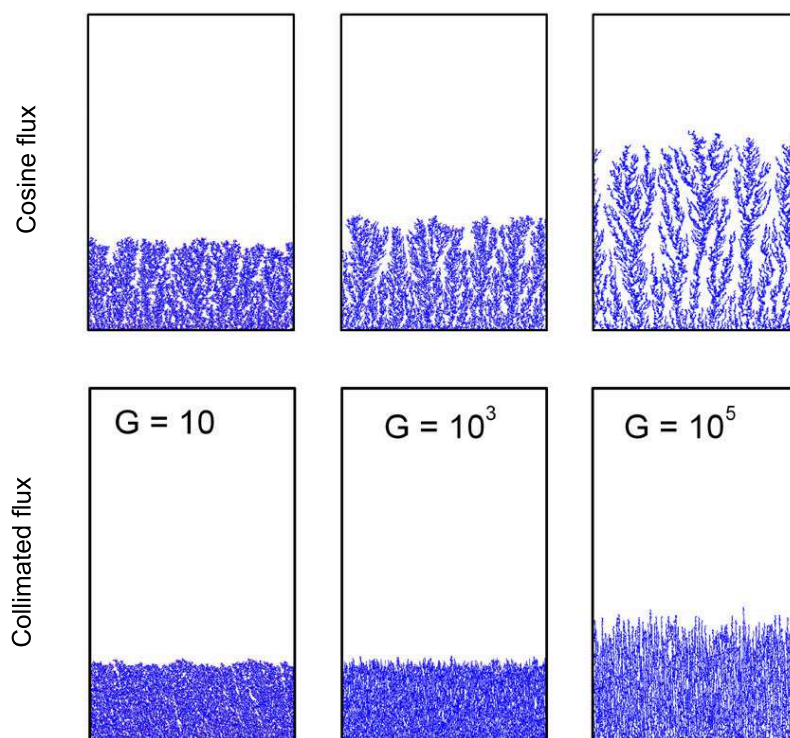


Figure 3. Effect of the flux incident angle on the VDP growth model. While the VDP growth with the cosine flux shows the characteristic columnar structures (top panels), such structures disappear when the incident angle sets zero, i.e., the vertically collimated flux (bottom panels). From left to right, $G = 10, 10^3$, and 10^5 for $L = 512$ at $t = 180$ ML.

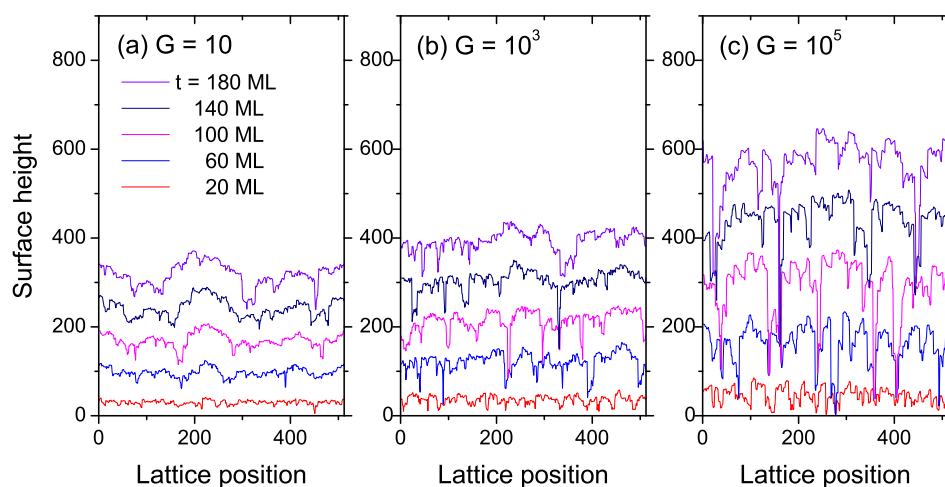


Figure 4. Evolution of surfaces in the VDP growth model. For $L = 512$, (a) $G = 10$, (b) $G = 10^3$, and (c) $G = 10^5$ at $t = 20, 60, 100, 140$ and 180 ML from bottom to top, respectively.

3. Numerical Results

We perform numerical simulations of with various system sizes up to $L = 1024$ for three values of G , where numerical data are averaged over 100 samples. Unlike the PVD/MBE growth model case, the VDP growth model case requires the active end site tracking and the polymer indexing, so that the largest system size in our MC simulations becomes much smaller than that in ordinary surface growth models.

3.1. Surface roughness and height-difference correlation function

We first measure the surface roughness (width) defined as

$$W^2(t) \equiv \overline{\langle [h(x, t) - \bar{h}(t)]^2 \rangle},$$

where \bar{f} is the spatial average, i.e., $\bar{f} = \frac{1}{L} \sum_x f(x)$, and $\langle \dots \rangle$ represents the statistical sample average. The width $W(t)$ in the VDP growth for $G = 10$ plotted in Fig. 5 (a), which shows clearly three regimes as L increases: the initial growth, the VDP growth, and the saturation. Unlike the conventional surface growth, the VDP growth exhibits anomalous dynamic scaling, where the VDP growth regime appears after about 5 monolayers (ML), irrespectively of the system sizes, and it undergoes some unusual behavior before $W(t)$ saturates to W_{sat} due to the finite-size effect. The global dynamic scaling of the VDP surface roughness is governed by the global roughness exponent α_{global} from the system size dependency of the saturated width ($W_{\text{sat}} \sim L^{\alpha_{\text{global}}}$) and the global dynamic exponent z_{global} from the system size dependency of the saturation time ($t_{\text{sat}} \sim L^{z_{\text{global}}}$).

In order to investigate the local dynamic scaling of the VDP growth, we also measure the two point height-difference correlation function defined as

$$C_2(r, t) = \overline{\langle |h(x+r, t) - h(x, t)|^2 \rangle},$$

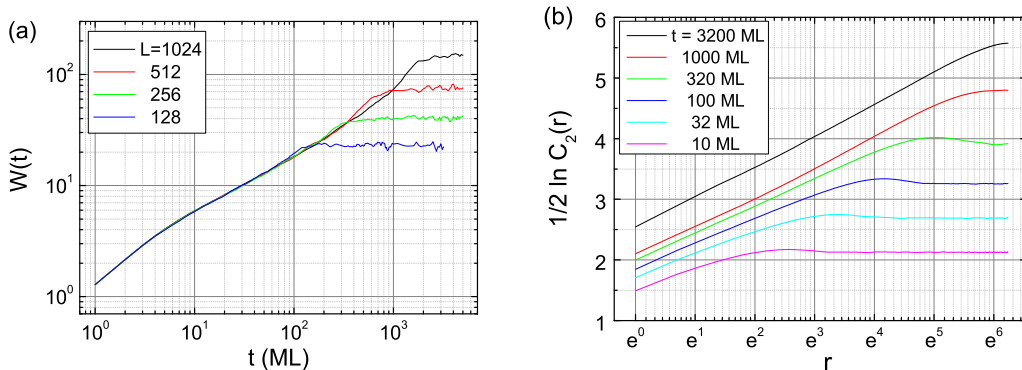


Figure 5. Double-logarithmic plots of W and C_2 for the case of $G = 10$. (a) surface roughness versus time for $L = 128, 256, 512$, and 1024 from bottom to top, and (b) height-difference correlation function versus r for $L = 1024$.

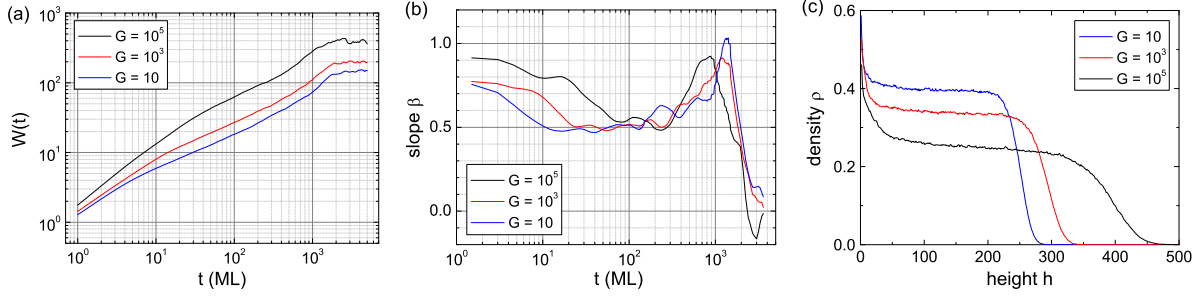


Figure 6. For $L = 1024$, (a) double-logarithmic plots of W against t , (b) semi-logarithmic of the effective growth exponent β against t , (from bottom to top, $G = 10, 10^3$, and 10^5), and (c) the density profile at $t = 100$ ML against surface height h (from top to bottom, $G = 10, 10^3$, and 10^5).

which follows $C_2(r, t) \sim r^{2\alpha_{\text{local}}}$ for $r < \xi(t)$ and $C_2(r, t) = 2W^2(t)$ for $r > \xi(t)$. Here $\xi(t)$ is the correlation length, scaling as $\xi(t) \sim t^{1/z_{\text{local}}}$. Figure 5 (b) shows how height correlations and the correlation length are developed at various times for $G = 10$. For three values of G , the global scaling behavior in the VDP growth is compared with the local one. Figure 6 shows clearly that as G increases, the surface becomes rough much fast with the large value of W , and less dense at each level of surface height. Moreover, from Fig. 6 (b) and (c), we observe that the initial growth regime gets extended as G increases, while at the real scaling regime by the VDP growth, the effective growth exponent β becomes all the same as $\beta \simeq 0.5 (\neq \alpha_{\text{global}}/z_{\text{global}})$, irrespectively of the value of G . This implies that at the early stage of the growth, the shadowing effect by the cosine flux is negligible since there are not many polymers, but later on, the shadowing effect governs the surface growth as well as the active bonding once polymers form. In the VDP growth regime, the density profile at each height level shows the difference of dynamic process such like a stratum reflects the historical event (see Fig. 6 (c)). Until a polymer forms, the effect of cosine flux is negligible and the monomer diffusion is

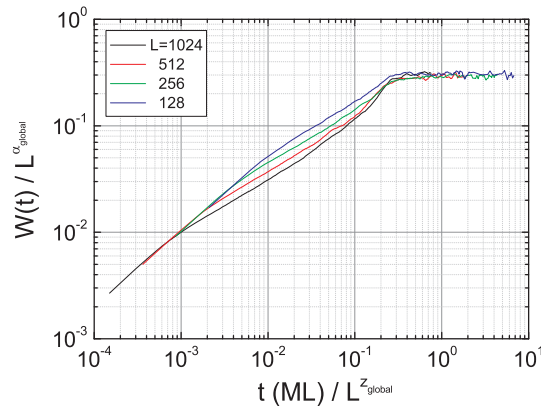


Figure 7. Data collapse of surface roughness: double-logarithmic plots of $WL^{\alpha_{\text{global}}}$ versus $t/L^{z_{\text{global}}}$ with $\alpha_{\text{global}} = 0.89$ and $z_{\text{global}} = 1.27$ for $G = 10$.

Table 1. Summary of roughness exponents and dynamic exponents for various G : Unlike the global results, the local results seems to be independent of the G value.

G	α_{global}	α_{local}	z_{global}	z_{local}
10	0.89(1)	0.50(2)	1.27(1)	1.27(2)
10^3	0.87(1)	0.47(2)	1.16(1)	1.27(2)
10^5	0.72(1)	0.48(2)	0.81(1)	1.32(2)

dominant, which explains the first decay in the density profile. After surface height becomes comparable to the characteristic length of polymer for a given G value, so that there are several structures of polymer lumps, the incident monomer with a certain angle can hang on the other polymer bodies and both the effect of the cosine flux and the diffusion of monomers governs the growing dynamics, which represents the plateau in the density profile. Finally, the front of surface is governed by the fluctuations of the location of active ends, which is shown as the second decay in the density profile. We like to note here that the density profile is taken at $t = 100$ ML, which corresponds to the same as the right side panels in Fig. 2.

Although the qualitative behavior of kinetic roughening seems to be similar for all three cases of G , its quantitative behavior quite depends on the value of G . Such a role of diffusion in the VDP growth is summarized as the G -dependent kinetic roughening in Table 1, in terms of the roughness exponent, α , and the dynamic exponent, z for both the global and local ones. It should be noticed that the growth exponent β we found above is different from either $\alpha_{\text{global}}/z_{\text{global}}$ or $\alpha_{\text{local}}/z_{\text{local}}$. Therefore, the data of W hardly collapse due to the VDP growth regime (see Fig. 7).

3.2. Height and step distributions

As measuring the height distribution, $P(h')$ where $h' = h - \langle h \rangle$, for various times and system sizes, we double check anomalous kinetic roughening in our VDP growth model and also confirm our numerical finding of α_{global} by collapsing the data (see Fig. 8) of $P(h')$. The height distribution becomes broader as time elapses, which means the surface gets rough with the large value of the width W since W corresponds to the standard deviation of $P(h')$. At the initial stage, $P(h')$ is almost Gaussian and symmetric, while at the final stage, the distribution is slightly skewed at right, where the exponential decay tail at the below side of the average height (left) is broader than that at its above side (right).

It is observed that anomalous kinetic roughening in the VDP growth is attributed to the power-law distribution of the height difference between the nearest-neighboring sites, i.e., $r = 1$ (namely “step”), $P(\Delta h)$, which implies that the VDP growth exhibits multifractality as well as $\alpha_{\text{global}} \neq \alpha_{\text{local}}$. We investigate how the power-law behavior of $P(\Delta h)$ changes as t elapses and as G increases, respectively. Figure 9 shows that for

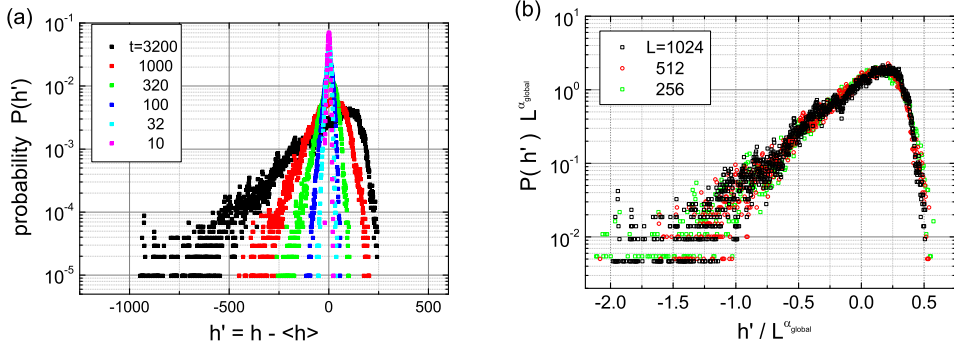


Figure 8. (a) Semi-logarithmic plots of the height distribution function, $P(h')$ against $h' = h - \langle h \rangle$ at various times, $t = 10, 32, 100, 320, 1000,$ and 3200 ML for $L = 1024$ and $G = 10$. Note that $\langle h \rangle = \bar{h}$ for our case. As t elapses, $P(h')$ becomes broader and gradually transformed into the right skewed Gaussian distribution. (b) At $t = 3200$ ML after the surface roughness gets saturated, $P(h')$ exhibits the scaling behavior by α_{global} , which is confirmed for various system sizes $L = 256, 512,$ and 1024 as $P(h')L^{\alpha_{\text{global}}}$ versus $h'/L^{\alpha_{\text{global}}}$ with $\alpha_{\text{global}} = 0.89$ for $G = 10$.

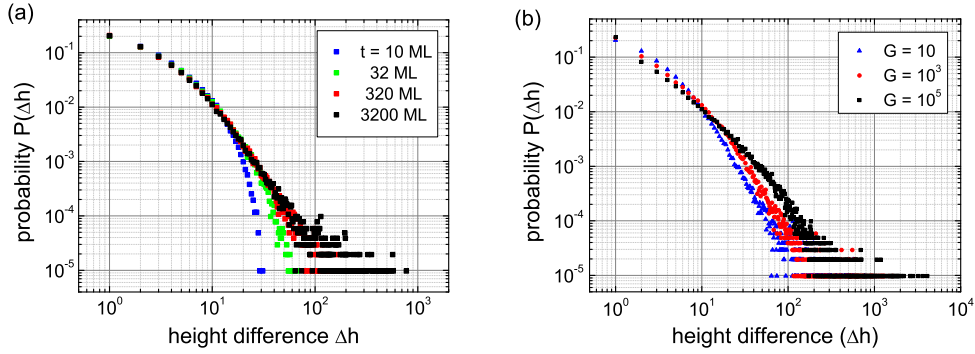


Figure 9. Power-law step distributions for $L = 1024$: (a) at various times only for $G = 10$ and (b) for three values of G only at $t = 3200$ ML.

the large values of Δh the decay exponent seems to be independent of the G value in the steady-state limit. It is very interesting that the step distribution shows clearly a power-law decay for large values $\Delta h (\equiv |h(x+1) - h(x)|)$ after W gets saturated.

This is somewhat similar to that in the ballistic deposition model with a power-law noise [10]. In that sense, we suspect that the active ends play a crucial role in the power-law step distribution, the details of which are under investigation [11].

3.3. Polymer Properties

In the VDP growth, the properties of polymer are also important to be discussed. As measuring the time-dependent frequency of the polymers per each site, $D(L_p)$, where L_p is the length of polymer for $L = 1024$ as well as the end-to-end distances (see Fig. 10), we finally investigate such properties. As time elapses, monomers are deposited on the surface more and more, so that the number of polymers increases and at the same time

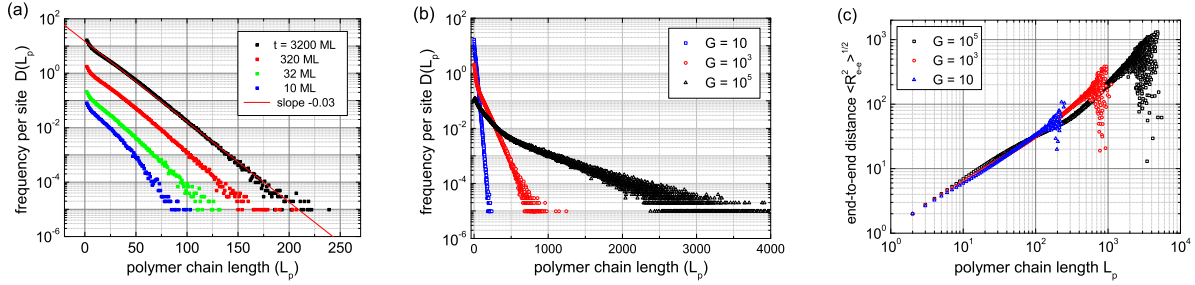


Figure 10. Semi-logarithmic plots of the polymer chain length distribution $D(L_p)$ against the length of polymer L_p (a) for $G = 10$ at various times and (b) for various G values at $t = 3200$ ML, where $L = 1024$. In the same setup of (b), (c) double-logarithmic plots of the end-to-end distance of polymer, $\langle R_{e-e}^2 \rangle^{1/2}$, against L_p .

polymers get longer. Based on our numerical finding, there is a typical length scale of polymers for a given value of G in the steady state of the VDP growth. It is observed that the typical length of a polymer gets longer as G increases (see Fig. 10 (b)). For an example, one typical polymer consists of about 15 monomers at $G = 10$, while 434 monomers at $G = 10^5$. Figure 10 (c) shows that the root-mean-square of the end-to-end distance for a given polymer, $\langle R_{e-e}^2 \rangle^{1/2}$, scales as $\langle R_{e-e}^2 \rangle^{1/2} \propto L_p^\nu$, where we find that the exponent ν is about 0.75 for short polymers under about 100 monomer length, but 1.0 for long polymers. Therefore, as G increases, it is observed that the crossover from $\nu = 0.75$ to $\nu = 1$. Here, the exponent ν represents the inverse of the fractal dimension of polymers. One can say $D_f = 1.33$ at $G = 10$, which is the same as that of the linear polymers formed by self-avoiding walk [2]. The detailed analysis has been investigated [11].

3.4. Growth of (2+1)-dimensional VDP thin films

The (2+1)-dimensional version of our model has been also considered in order to explain the most recent experimental results by Lee and his coworkers [6], where the growth of PPX-C films was discussed. It is noted that our extended version can be considered as the modification of the earlier study by Zhao and his coworkers [12] for the VDP process in the submonolayer regime. In our extension, the multilayer growth is allowed with the coalescence process of polymers. Our preliminary results in a (2+1)-dimensional lattice [13] seems to be quite different from that in a (1+1)-dimensional lattice, but they also exhibit anomalous scaling behavior in kinetic roughening with multifractality, which is similar to the experimental results, except that the valley filling regime seems to be missing in our model study. To answer the origin of the valley filling regime of the experimental results, it might be necessary that we also consider some new dynamics, such as chain relaxations we ignored in our current version. Regarding polymer properties in the VDP growth would be another key to identify the universality class of the VDP growth more clearly. For example, we suspect that the reptation with zigzag paths governs the sublinear scaling behavior at early stage of the polymer

growth, while the polymer interaction become relevant after polymers grow enough to be comparable with the typical length, so that the coalescence of polymers let them show the linear scaling as shown in the (1+1)-dimensional version. Such properties have been also investigated in our modified version in a (2+1)-dimensional lattice [13].

4. Summary and Remarks

In summary, we studied a simple toy model for the growth of polymer thin films by vapor deposition polymerization (VDP) processes in order to explain recent experimental results for the coating processes of poly (p-xylylene) (PPX) and the derivatives, e.g., PPX-C. It is found that the VDP growth is quite different from the conventional molecular beam epitaxy (MBE) growth for the growth of metal or semiconductor films. In particular, we argued that anomalous scaling behavior in kinetic roughening for the VDP growth is attributed to the instability induced by the nonlocal shadowing effects as well as active bonding in polymerization. As another clear evidence of such anomalies, we showed the power-law step distributions, which is directly related to the multifractality of the VDP growth. The two-point height difference q -th moment analyses are also under detailed investigation [11, 13].

Acknowledgments

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